

Figure 1. Cross-section TEM image laterally ordered *h*BN film: (a) blanket film on Si substrate and (b) trench patterned substrate.

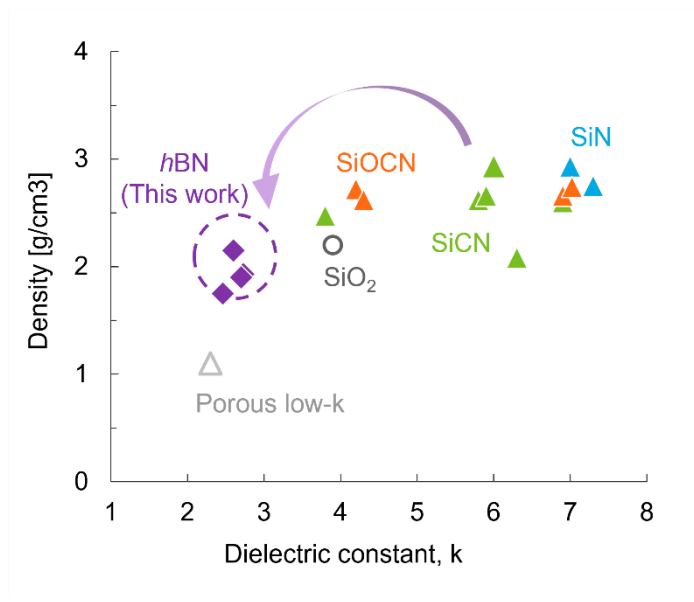


Figure 2. Summary of the dielectric constants and film densities of Si-based films (SiO<sub>2</sub>, SiN, SiCN, SiOCN), porous low-k films, and *h*BN (this work).